

ABSTRACT OF THE DISCLOSURE

A photoresist pattern with a reinforcing section, provided with a line section 2 and a reinforcing section 3 that continues to the line section and that has a greater width than a line width of the line section is formed by forming on a substrate a photoresist film, exposing the photoresist film and then developing. As a result, fine line shaped photoresist patterns are prevented from collapsing and being washed away.